Ontrak Systems Introduces New Cmp Copper Cleaning Solution

Ontrak Systems Introduces New Cmp Copper Cleaning Solution SAN JOSE, Calif., July 8, 1998 - OnTrak Systems, Inc., a wholly-owned subsidiary of Lam Research Corporation (Nasdaq: LRCX), today announced the introduction of Synergy Performa, a new copper CMP cleaning solution developed specifically to address challenges posed by the emergence of copper interconnect. Synergy Performa combines a production proven system with an advanced chemistry to address the multiple challenges of copper CMP cleaning.

“As the market leader in CMP cleaning, OnTrak has established a worldwide reputation for providing complete process solutions,” said Jerry Cutini, president of OnTrak. “Copper interconnect poses new challenges to the CMP process arena, especially in the area of cleaning. The introduction of Synergy Performa demonstrates OnTrak’s ability to develop process solutions well before IC makers fully implement advanced processes into production. Synergy Performa is yet another example of OnTrak’s commitment to advancing IC cleaning technology and enabling our global customers to implement next generation interconnect technology.”

Based on OnTrak’s flagship Synergy™ cleaning system, Synergy Performa offers a unique approach to copper CMP cleaning that combines an evolutionary system platform and advanced chemistry to provide optimum cleaning capabilities. This combination of system and cleaning chemistry removes contaminants from the front, back and bevel edge of the wafer.

“Synergy Performa combines the best of OnTrak’s double-sided scrubbing (DSS) cleaning technology with an internally developed copper cleaning chemistry to provide the first cleaning solution specifically tailored for copper CMP,” noted Dr. Diane Hymes, director of process technology at OnTrak. “The net result for IC makers implementing copper interconnect is a robust CMP cleaning process.”

OnTrak Systems, Inc., a wholly owned subsidiary of Lam Research Corporation, is a leading supplier of advanced wafer processing equipment to the worldwide semiconductor industry. The company primarily focuses on providing cleaning process solutions for CMP. OnTrak’s Double-Sided Scrubbing (DSS®) and Chemical Mechanical Cleaning (CMC) technologies are utilized for CMP cleaning in fabs worldwide. OnTrak is located in San Jose, California.

“Safe Harbor” Statement under the Private Securities Litigation Act of 1995. Except for historical information, this press release contains certain forward-looking statements and other prospective information relating to future events, including, but not limited to, statements and other information relating to the release of new products, the expectation future product success and significance of market acceptance, and OnTrak’s position generally in the CMP market. These forward-looking statements and other information are subject to various risks, uncertainties and changes in condition, significance, value and effect that could cause results to differ materially and in ways not readily foreseeable, including, but not limited to, continued uncertainty surrounding market conditions, product acceptance and market demand, and other risks detailed from time to time in the company’s SEC reports, including the report on Form 10-K for the year ended June 30, 1997, and the Form 10-Q for the quarter ended March 29, 1998. The company assumes no obligation to update the information in this Press Release.

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